

NICKEL/VANADIUM SPUTTERING TARGET WITH ULTRA-LOW ALPHA EMISSION

Abstract of the Disclosure

A nickel/vanadium sputter target for depositing magnetic nickel is provided having high homogeneity, high purity and an ultra-low level of alpha emission. Source materials having high purity and alpha emissions of equal or less than 10^{-2} counts/cm²-hr are melted and cast under a vacuum and low pressure, hot or cold rolled, and heat treated to form a sputter target having an alpha emission of equal or less than 10^{-2} counts/cm²-hr, and preferably less than 10^{-3} counts/cm²-hr. From this target may be deposited a thin film of magnetic nickel having an alpha emission equal or less than 10^{-2} counts/cm²-hr, preferably less than 10^{-3} counts/cm²-hr and more preferably less than 10^{-4} counts/cm²-hr.

Fig. 1